

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
L1	4	jp-11080708-.did. jp-2001288456-.did.	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	OFF	2004/12/22 08:27
L2	1	2001-551915.NRAN.	DERWENT	OR	OFF	2004/12/22 08:29
L3	1	(cmp (chemical\$4 near mechanical\$4)) and (hclo "hclo. sub.3" hclo3 "hclo.sub.4" hclo4 "hbro.sub.3" hbro3 "hio.sub.3" hio3 "hio.sub.4" hio4)	EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/12/22 08:52
L4	10	(cmp (chemical\$4 near mechanical\$4)) same (hclo "hclo. sub.3" hclo3 "hclo.sub.4" hclo4 "hbro.sub.3" hbro3 "hio.sub.3" hio3 "hio.sub.4" hio4)	US-PGPUB; USPAT	OR	ON	2004/12/22 08:53
L5	103	"5225034".URPN.	USPAT	OR	OFF	2004/12/22 08:55
L6	32	(cmp (chemical\$4 near mechanical\$4)) and (hocl (perchloric adj acid) (hypochlorous adj acid) hypochlorite (periodic adj acid) (perbromic adj acid) (chloric adj acid) (bromic adj acid) (iodic adj acid))	EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/12/22 08:58
L7	1	((cmp (chemical\$4 near mechanical\$4)) same (hocl (perchloric adj acid) (hypochlorous adj acid) hypochlorite (periodic adj acid) (perbromic adj acid) (chloric adj acid) (bromic adj acid) (iodic adj acid))) and (((word adj line) wordline) and ((cmp (chemical\$4 near mechanical\$4)) same (silicon polysilicon)))	US-PGPUB; USPAT	OR	ON	2004/12/22 09:02
L8	111	((word adj line) wordline) same ((cmp (chemical\$4 near mechanical\$4)) same (silicon polysilicon) same (spacer nitride) same ((contact hole opening) with (interlayer dielectric bpsg teos fsg psg usg oxide ild)))	US-PGPUB; USPAT	OR	ON	2004/12/22 09:05
L9	2	(cmp (chemical\$4 near mechanical\$4)) same (hocl (perchloric adj acid) (hypochlorous adj acid) hypochlorite (periodic adj acid) (perbromic adj acid) (chloric adj acid) (bromic adj acid) (iodic adj acid)) same (bpsg teos fsg psg usg polysilicon "poly-si" polycrystalline poly)	US-PGPUB; USPAT	OR	ON	2004/12/22 09:12

L10	30	(cmp (chemical\$4 near mechanical\$4)) same ("hno.sub.3" (nitric adj acid)) same (bpsg teos fsg psg usg polysilicon "poly-si" polycrystalline poly)	US-PGPUB; USPAT	OR	ON	2004/12/22 09:14
L11	73	(438/637.ccls. 438/675.ccls. 438/684.ccls. 438/692.ccls. 438/693.ccls. 252/79.1.ccls. 252/79.2.ccls.) and ((cmp (chemical\$4 near mechanical\$4)) same (hocl (perchloric adj acid) (hypochlorous adj acid) hypochlorite (periodic adj acid) (perbromic adj acid) (chloric adj acid) (bromic adj acid) (iodic adj acid)))	US-PGPUB; USPAT	OR	ON	2004/12/22 09:20
L12	11	((word adj line) wordline) same (nitride with (cap mask)) same (etch\$6 with ("ccl.sub.4" "cl.sub.2" (carbon adj tetrachloride) chlorine))	US-PGPUB; USPAT	OR	ON	2004/12/22 09:28
L13	9	((word adj line) wordline) same (nitride with spacer with (teos silane))	US-PGPUB; USPAT	OR	ON	2004/12/22 09:29
L14	41	bpsg with (etch\$6 with ("c.sub.4 f. sub.8" "c.sub.2 f.sub.6" "c.sub.3 f. sub.8"))	US-PGPUB; USPAT	OR	ON	2004/12/22 09:30
L15	1	(cmp (chemical\$4 near mechanical\$4)) with (silicon polysilicon) with (hard adj pad)	US-PGPUB; USPAT	OR	ON	2004/12/22 09:31
L16	8	(cmp (chemical\$4 near mechanical\$4)) same (silicon polysilicon) same (hard adj pad)	US-PGPUB; USPAT	OR	ON	2004/12/22 09:32